

<b>Session Title:</b>	<b>[TA3] Nanoscale Thin Film Deposition V</b>
<b>Session Date:</b>	<b>November 15 (Tue.), 2022</b>
<b>Session Time:</b>	<b>14:30-16:30</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Woojin Jeon (Kyung Hee Univ., Korea)</b>

**[TA3-1] [Invited] 14:30-15:00**

**New ALD Chemistry for Metals and Area Selective Deposition**

**Markku Leskelä, Timo Hatanpää, Chao Zhang, and Mikko Ritala (Univ. of Helsinki, Finland)**

**[TA3-2] [Invited] 15:00-15:30**

**Overview of ALD Precursors for Semiconductor Manufacturing**

**Wonyong Koh (UP Chemical Co., Ltd., Korea)**

**[TA3-3] 15:30-15:50**

**Development of New Metal Precursors for ALD**

**Ga Yeon Lee, Chanwoo Park, Heenang Choi, Sung Kwang Lee, Ji Yeon Ryu, Taeyong Eom, Bo Keun Park, Chang Gyoung Kim, and Taek-Mo Chung (KRICT, Korea)**

**[TA3-4] 15:50-16:10**

**Roles of Alkyl Halide in Atomic Layer Deposition toward Enhanced Film Conformality and Properties on High Aspect Ratio Substrate**

**Kok Chew Tan, Changbong Yeon, Seung Hyun Lee, Jaesun Jung, and Young-Soo Park (Soulbrain Co., Ltd., Korea)**

**[TA3-5] 16:10-16:30**

**Surface Reaction Mechanism of Atomic Layer Deposition of Niobium Oxide Using Tris(diethylamido)(tert-butylimido)niobium**

**Khabib Khumaini, Hyeonsu Roh, Hyunmin Han, Hye-Lee Kim (Sejong Univ., Korea), Hyo-Suk Kim, Jang-Hyeon Seok, Jung Woo Park (Hansol Chemical Co., Ltd., Korea), and Won-Jun Lee (Sejong Univ., Korea)**